

WEST Search History

DATE: Tuesday, December 03, 2002

<u>Set Name</u>	<u>Query</u>	<u>Hit Count</u>	<u>Set Name</u>
side by side			result set
	<i>DB=USPT,PGPB; PLUR=YES; OP=ADJ</i>		
L35	L27 and L8	383	L35
	<i>DB=USPT,PGPB,JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>		
L34	((hot filament) or thermionic or (hot cathode)) with ((clean\$3 or etch\$3) near4 (chamber or wall or vessel or reactor or apparatus))	10	L34
L33	((hot filament) or thermionic or (hot cathode)) with ((clean\$3 or etch\$3) near2 gas\$4)	8	L33
L32	L31 and L8	93	L32
L31	(\$3CVD or (vapor near2 (deposit\$3))) and ((clean\$3 or etch\$3 or remov\$5 near3 (coat\$3 or film or deposit\$3 or layer or residue or contamin\$6))) near4 (chamber or reactor or wall or vessel or apparatus)) and ((hot or heat\$3 or (high temperature) or thermionic) near3 (cathode or element or filament or wire or mesh) near6 (etch\$3 or clean\$3 or gas\$4))	387	L31
L30	((Pt or platinum) with (cathode or ((heat\$3 or hot) element) or filament or thermionic or wire or mesh)) same ((clean\$3 or etch\$3) near3 gas\$4)	12	L30
	<i>DB=JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>		
L29	((clean\$3 or etch\$3 or (remov\$5 near3 (coat\$3 or film or deposit\$3 or layer or residue or contamin\$6))) near4 (chamber or reactor or wall or vessel or apparatus)) and ((hot or heat\$3 or (high temperature) or thermionic) near3 (cathode or element or filament or wire or mesh) near6 ((etch\$3 or clean\$3) near2 gas\$4))	12	L29
	<i>DB=USPT,PGPB; PLUR=YES; OP=ADJ</i>		
L28	(\$3CVD or (vapor near2 (deposit\$3))) and ((clean\$3 or etch\$3 or (remov\$5 near3 (coat\$3 or film or deposit\$3 or layer or residue or contamin\$6))) near4 (chamber or reactor or wall or vessel or apparatus)) and ((hot or heat\$3 or (high temperature) or thermionic) near3 (cathode or element or filament or wire or mesh) near6 ((etch\$3 or clean\$3) near2 gas\$4))	10	L28
L27	(\$3CVD or (vapor near2 (deposit\$3))) and ((clean\$3 or etch\$3 or (remov\$5 near3 (coat\$3 or film or deposit\$3 or layer or residue or contamin\$6))) near4 (chamber or reactor or wall or vessel or apparatus)) and ((hot or heat\$3 or (high temperature) or thermionic) near3 (cathode or element or filament or wire or mesh))	2026	L27
L26	L25 and L8	480	L26
L25	(\$3CVD or (vapor near2 (deposit\$3))) and ((clean\$3 or etch\$3 or remov\$5) near4 (chamber or reactor or wall or vessel or apparatus)) and ((hot or heat\$3 or (high temperature) or thermionic) near3 (cathode or element or filament or wire or mesh))	2918	L25

L24	(\$3CVD or (vapor near2 (deposit\$3))) and ((clean\$3 or etch\$3 or remov\$5) near4 (chamber or reactor or wall or vessel or apparatus)) and ((hot or heat\$3 or (high temperature) or thermionic or Pt or platinum) near3 (cathode or element or filament or wire or mesh))	3120	L24
L23	L8 and ((insitu or (in situ) or (in-situ)) near3 clean\$3)	170	L23
<i>DB=USPT,PGPB,JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>			
L22	((insitu or (in situ) or (in-situ)) near3 clean\$3) and ((hot or heat\$3 or (high temperature) or thermionic) near3 (cathode or element or filament or wire or mesh))	134	L22
L21	((insitu or (in situ) or (in-situ)) near3 clean\$3) and ((Pt or platinum) with (cathode or ((heat\$3 or hot) element) or filament or thermionic or wire or mesh))	12	L21
<i>DB=USPT,PGPB; PLUR=YES; OP=ADJ</i>			
L20	L9 and ((insitu or (in situ) or (in-situ)) near3 clean\$3)	8	L20
<i>DB=JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>			
L19	L18 and (\$5CVD or (vapor near2 (coat\$3 or deposit\$3)))	16	L19
L18	((etch\$3 or remov\$3 or clean\$3) near5 (wall or chamber or apparatus or gas or vessel or reactor or surface) near7 (coat\$3 or deposit\$3 or film or layer or contamin\$6 or residue or (build up) or buildup)) and ((hot or heat\$3 or (high temperature) or thermionic) near3 (cathode or element or filament or wire or mesh) with (etch\$3 or clean\$3 or remov\$4))	318	L18
<i>DB=USPT,PGPB; PLUR=YES; OP=ADJ</i>			
L17	L8 and ((etch\$3 or remov\$3 or clean\$3) near5 (wall or chamber or apparatus or gas or vessel or reactor or surface) near7 (coat\$3 or deposit\$3 or film or layer or contamin\$6 or residue or (build up) or buildup)) and ((hot or heat\$3 or (high temperature) or thermionic) near3 (cathode or element or filament or wire or mesh) with (etch\$3 or clean\$3 or remov\$4))	97	L17
L16	L8 and ((etch\$3 or remov\$3 or clean\$3) near5 (wall or chamber or apparatus or gas or vessel or reactor or surface or coat\$3 or deposit\$3 or film or layer)) and ((hot or heat\$3 or (high temperature) or thermionic) near3 (cathode or element or filament or wire or mesh) with (etch\$3 or clean\$3 or remov\$4))	143	L16
L15	L8 and ((Pt or platinum) with (cathode or ((heat\$3 or hot) element) or filament or thermionic or wire or mesh))	71	L15
L14	L9 and ((hot or heat\$3 or (high temperature) or thermionic) near3 (cathode or element or filament or wire or mesh))	16	L14
L13	L9 and ((Pt or platinum) with (cathode or ((heat\$3 or hot) element) or filament or thermionic or wire or mesh))	1	L13
L12	L6 and ((etch\$3 or remov\$3 or clean\$3) near5 (wall or chamber or apparatus or gas or vessel or reactor or surface or coat\$3 or deposit\$3 or film or layer))	21	L12
L11	L6 and ((etch\$3 or remov\$3 or clean\$3) near5 (wall or chamber or apparatus or gas or vessel or reactor or surface))	19	L11

L10	L6 and (Pt or platinum)	3	L10
L9	(L4 or L5 or L6) and L7	95	L9
L8	(L4 or L5 or L6 or L7)	7640	L8
L7	((216/37).icls. or (216/63).icls. or (216/64).icls. or (216/67).icls. or (216/71).icls. or (134/19).icls. or (134/1.3).icls. or (134/1).icls. or (134/22.1).icls. or ((134/37)!.ICLS.))	3155	L7
L6	((118/723HC)!.ICLS.)	34	L6
L5	((118/715).icls. or (118/719).icls. or (118/722).icls. or ((118/723R)!.ICLS.))	2717	L5
L4	((427/561).icls. or (427/562).icls. or (427/585).icls. or (427/587).icls. or (427/592).icls. or (427/237).icls. or (427/248.1).icls. or (427/255.23).icls. or ((427/255.28)!.ICLS.))	2108	L4
L3	(5849092 5926743 6143128 6201219 6242347 6255222)! [pn]	6	L3
<i>DB=JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>			
L2	(anelva or ishibashi) and ((hot or heat\$3 or Pt or platinum) near3 (element or filament)) and (remov\$5 near5 (coat\$3 or deposit\$3 or film or layer))	5	L2
<i>DB=USPT,PGPB; PLUR=YES; OP=ADJ</i>			
L1	6375756.pn.	1	L1

END OF SEARCH HISTORY